## Molecular dynamics study on defect formation in SiC film

Kenji Nishimura<sup>1</sup>), Koji Miyake<sup>1</sup>), and Ken-ichi Saitoh<sup>2</sup>) 1) National Institute of Advanced Industrial Science and Technology (AIST) 2) Kansai University

## Highlights

- Our molecular dynamics simulations have revealed the dependence of temperature and crystallographic orientation on defect formation in single crystalline SiC.
- High temperature causes the transition of formed defects from perfect dislocations to partial dislocations with stacking faults.
- Impressions after nanoindentation exhibit obvious crystal anisotropy on its symmetry and pileup patterns.

### Introduction

Silicon carbide (SiC) is a promising candidate as a semiconductor for nextgeneration power electronics devices. Despite numerous experimental studies, it is still a great challenge to understand mechanical properties and defect formation process at an atomistic level. Objectives: To clarify plastic deformation mechanism and defect formation criteria in SiC.

#### Nanoindentation<sup>1</sup>

#### Nanoscratch<sup>2</sup>







### Results and discussion

### Load – displacement curves

(001) indent





Transition from pure elastic to elastic-plastic deformation, known as pop-in event, is observed. Elastic response does not depend on temperature. In contrast, elastic-plastic curves shift downward with increasing temperature.



# <u>Pop-in criteria</u>

<sup>1</sup>Matsumoto *et al.*, J.Phys. D: Appl. Phys. **50**, 265303 (2017). <sup>2</sup>Sako *et al.*, J. Appl. Phys. **119**, 135702 (2016).

### Method

## Nanoindentation



Simul	lation	conditions

Property	Value
Temperature [K]	300, 1000 1500, 2000
Number of atom	1150000
Indenter radius [nm]	8.72
Indent surface	(001), (111)
Pushing speed [m/s]	1.0
Maximum depth [nm]	5.0

Extended CNA analysis



### DXA analysis<sup>3</sup>





(001) indent

(111) indent

Projected contact surface is circle even at high temperature. (111) plane has higher resistance against plastic deformation than (001) at lower temperature.

DXA

## Characteristics of lattice defects, (111)

Extended CNA



## 300 K 2000 K

● HCP ● BCC ● Other



2000 K

- Partial — Other — Perfect

Perfect dislocations are dominant at low temperature, whereas partial dislocations with stacking faults dramatically increase at high temperature.

SiC crystal structure is composed of the superposition of Si and C sublattice. After removing C atoms, CNA (Common Neighbor Analysis) is applied to Si sublattice. DXA (Dislocation Extraction Algorithm) identify all dislocations in crystal, determine their Burgers vectors, and output dislocation lines.

<sup>3</sup>A. Stukowski *et al.*, Modelling Simul. Mater. Sci. Eng. **20**, 085007 (2012).

